PROCESSING APPARATUS AND PROCESSING METHOD

ABSTRACT OF THE DISCLOSURE

A development processing apparatus includes a processing unit for storing a substrate S and a processing solution supply nozzle arranged above the substrate S stored in the processing unit. A processing solution storage is formed inside the supply nozzle. A supply passage for supplying the processing solution into the solution storage is connected to the supply nozzle. A plurality of eject holes for ejecting the processing solution in the solution storage are formed in a lower surface of the supply nozzle. In this processing apparatus, the upper surface of the solution storage consists of at least one inclined surface, and an exhaust port is formed in a high portion of the inclined surface.

Fig. 2